

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE****PATENT**In re application of: Ricci *et al.*Attorney Docket No.:  
LAM1P118/P0539

Application No.: 09/408,921

Examiner: A. Powell

Filed: September, 30, 1999

Group: 1763

Title: PRETREATED GAS DISTRIBUTION PLATE

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NW**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being  
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DC 20231 on November 6, 2001.

Signed: Deborah Neill

Deborah Neill

**AMENDMENT B**

Commissioner for Patents  
Box Non-Fee Amendment  
Washington, D.C. 20231

Sir:

This is in response to the Office Action mailed August 6, 2001.  
Reconsideration of the captioned application is respectfully requested.

**IN THE CLAIMS:**

Please AMEND claims 1, 5, 7, 8, 12-15 and 38-39 as follows:

1. (Twice Amended) A gas distribution plate for use in a semiconductor fabrication apparatus including a semiconductor processing chamber, the gas distribution plate comprising:

a plurality of holes for passing process gases to the semiconductor processing chamber; and

B1  
S2X  
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a portion exposed to the process chemistry used in the semiconductor fabrication apparatus, wherein the portion of the gas distribution plate has substantially no micro-defects about 50 micrometers or greater, after machining, that may lead to contamination of a wafer located within said semiconductor processing chamber.

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